



AZ 1529 photoresist

Product	AZ 1529 photoresist
Manufacturer	EMD Performance Materials Corp.
Composition	65–70% 1-Methoxy-2-propanol acetate , 5–10% Diazonaphthoquinonesulfonic ester , 0 - 0.3% 2-Methoxy-1-propanol acetate , 25–30% Cresol novolak resin ; liquid
Synonyms	
Typical Uses	Positive-tone photoresist for broadband and g/h/i-line exposure
Hazards	<div style="text-align: center;"></div> <p>202</p> <p>Serious eye damage/eye irritation CATEGORY 2A</p> <p>Flammable liquids CATEGORY 3</p> <p>Specific target organ toxicity – single exposure CATEGORY 3</p>
Storage	Working volumes in amber bottles, stored in primary litho area; stock bottles in resist fridge outside W1-040
Disposal	Solid: Organic waste / organic sharps waste containers in primary or secondary litho areas. Liquid: solvent waste bottles in litho wet decks or wet decks 1A/1B/2A.
Comments	Standard recipe yields ~3.4 μm resist thickness.
Status	STOCKED



Check First

Please contact a nanoFAB staff member for uses not listed above.

Additional information

- [AZ 1500 series datasheet](#)